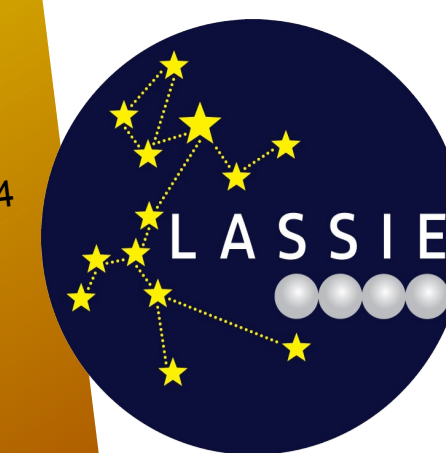


Diffusion and reactivity of O and O₂

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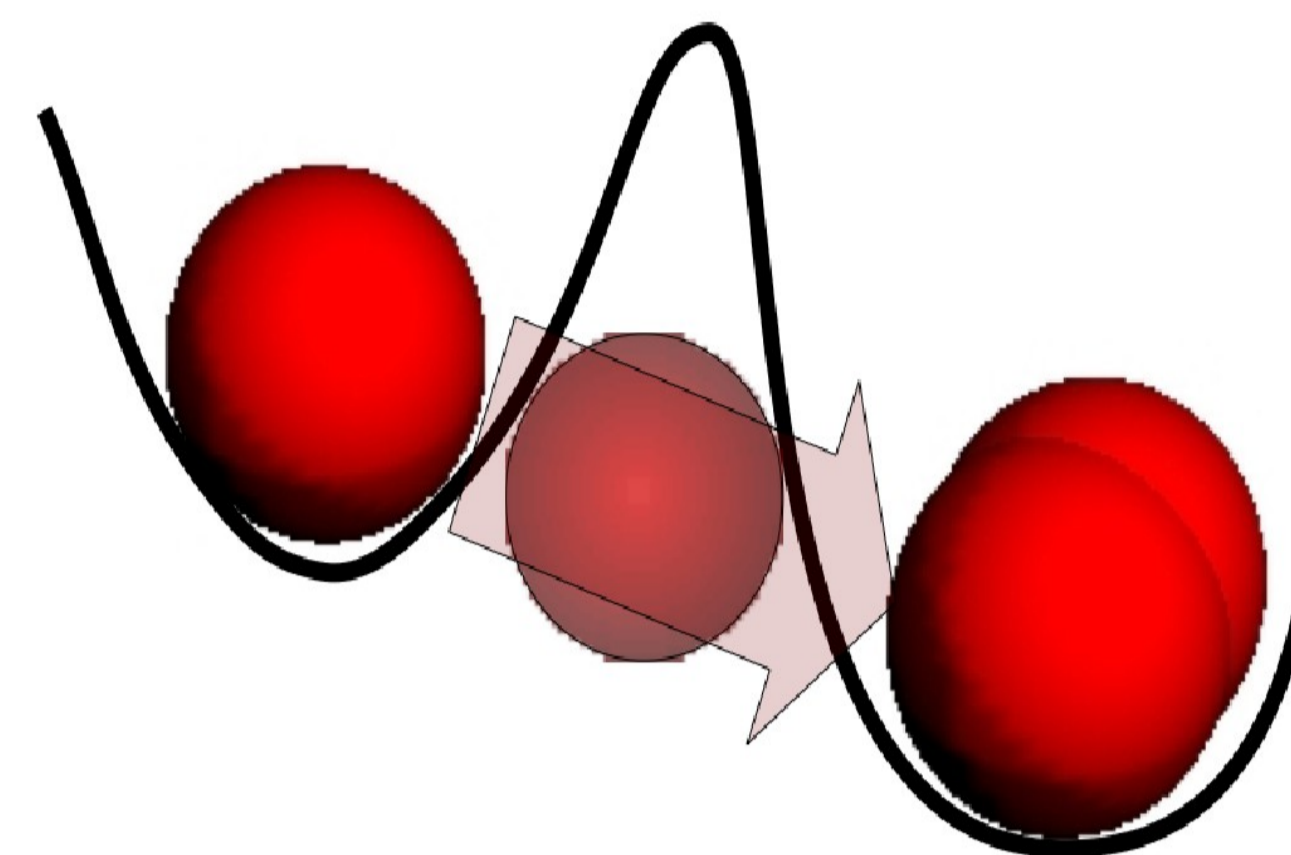
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O Diffusion

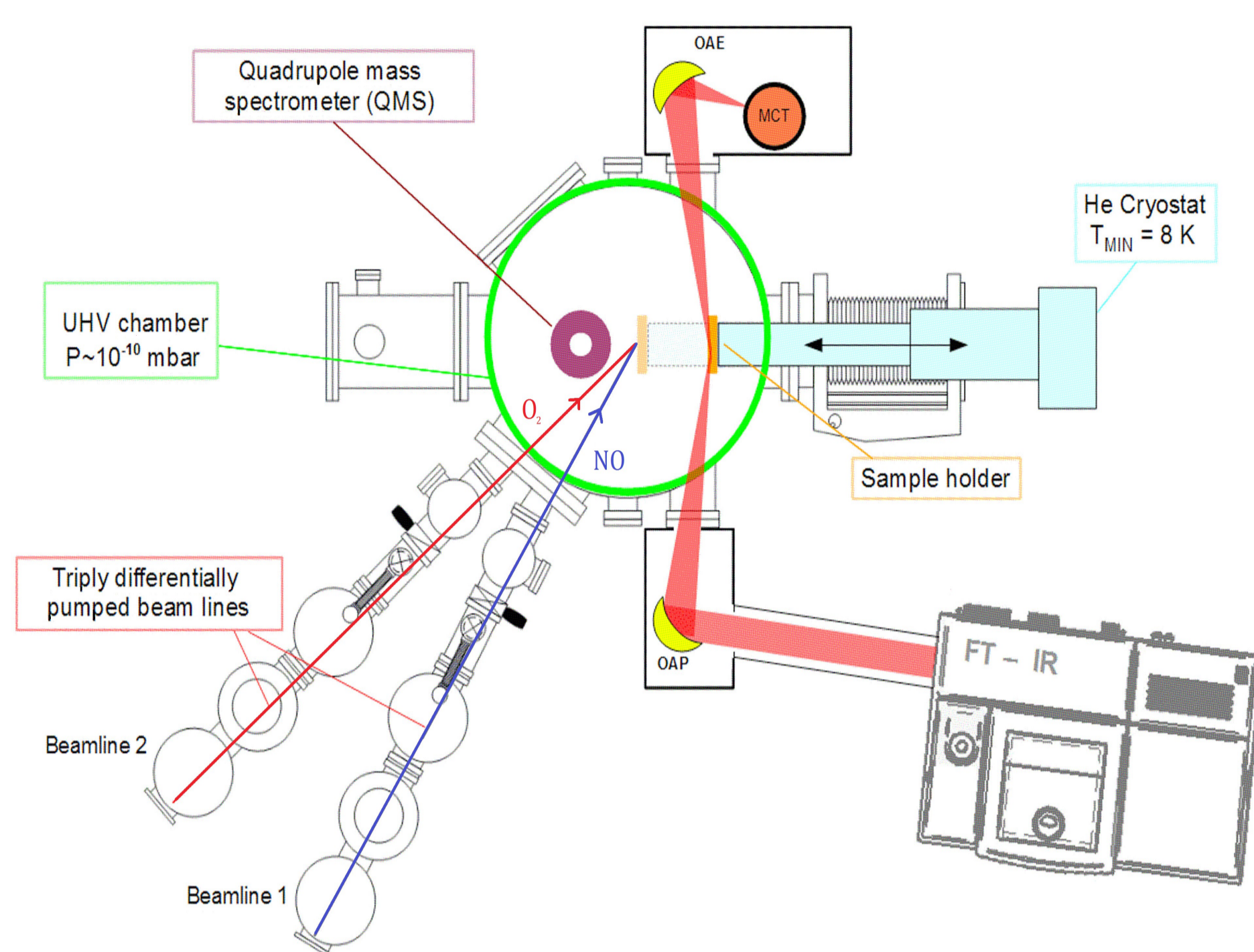
The solid state astrochemistry at low temperature is governed by the possibility of reactants to meet each others. Hydrogenation of numerous species such as H, CO, NO, O₂, O₃ ... as been the subject of recent intense experimental investigations. We propose now to focus for the first time on oxidation.



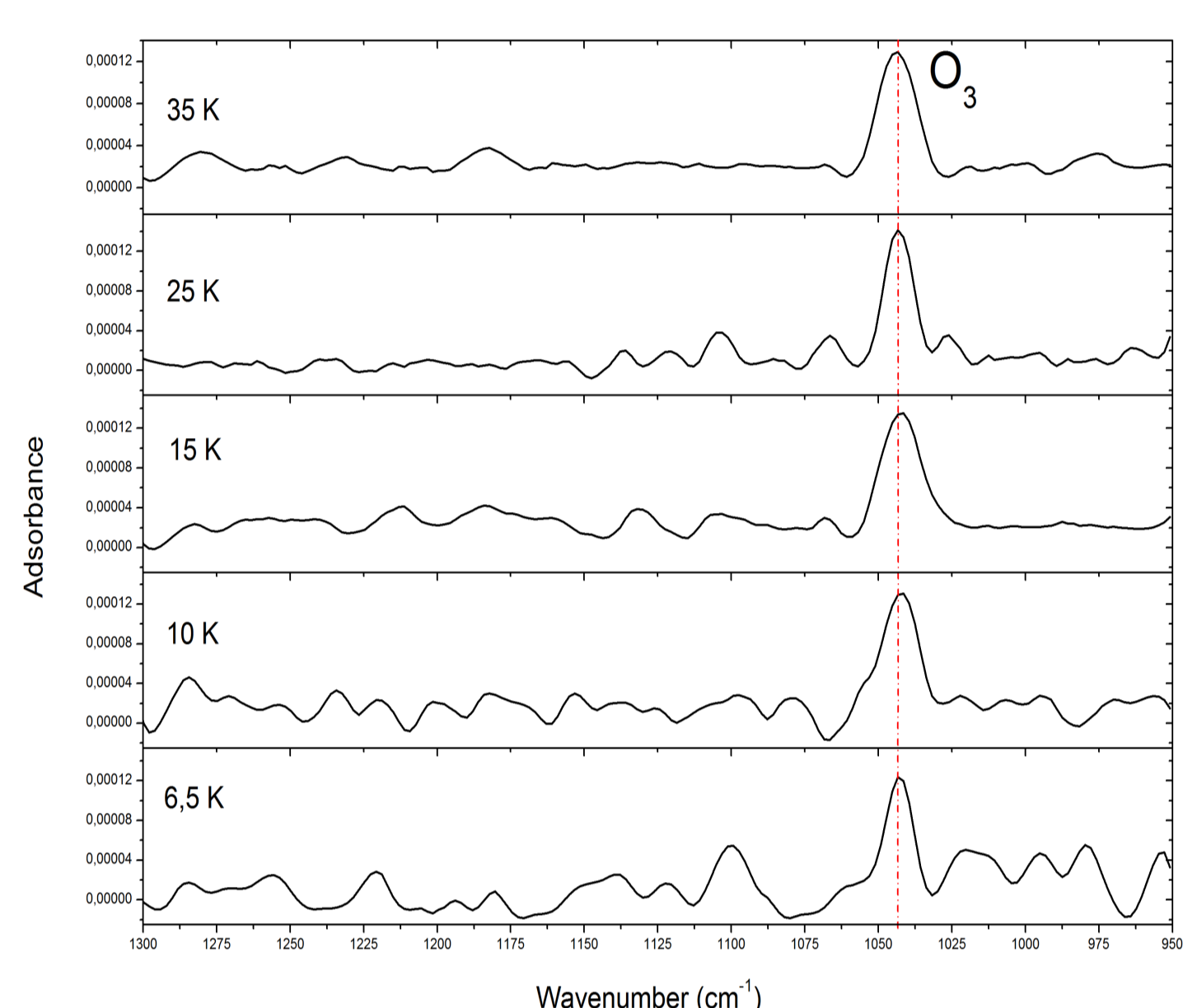
We have found that the O+O reaction and the O+O₂ reaction are limited by diffusion of O atoms on the substrate. We derive the diffusion temperature law and observe, like in quantum physics handbooks, the dramatic transition from quantum to classical diffusion. Despite of the high mass of O, quantum tunneling is efficient even at 6K. As a consequence, the solid-state astrochemistry of cold regions should be reconsidered.

FORMOLISM

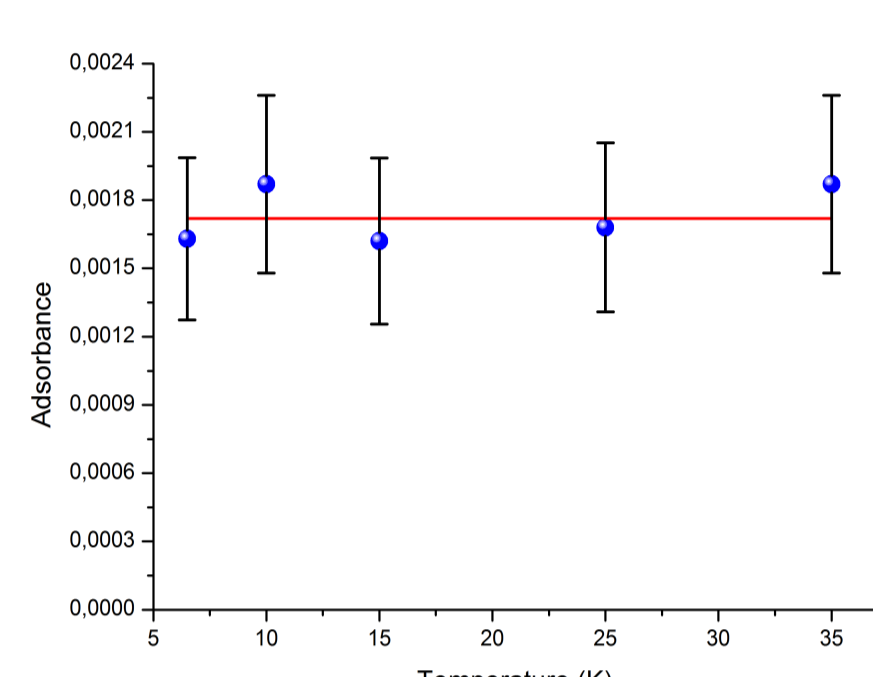
The products are probed using Temperature Programmed Desorption (TPD) and Reflexion Absorption Infrared Spectroscopy (RAIRS).



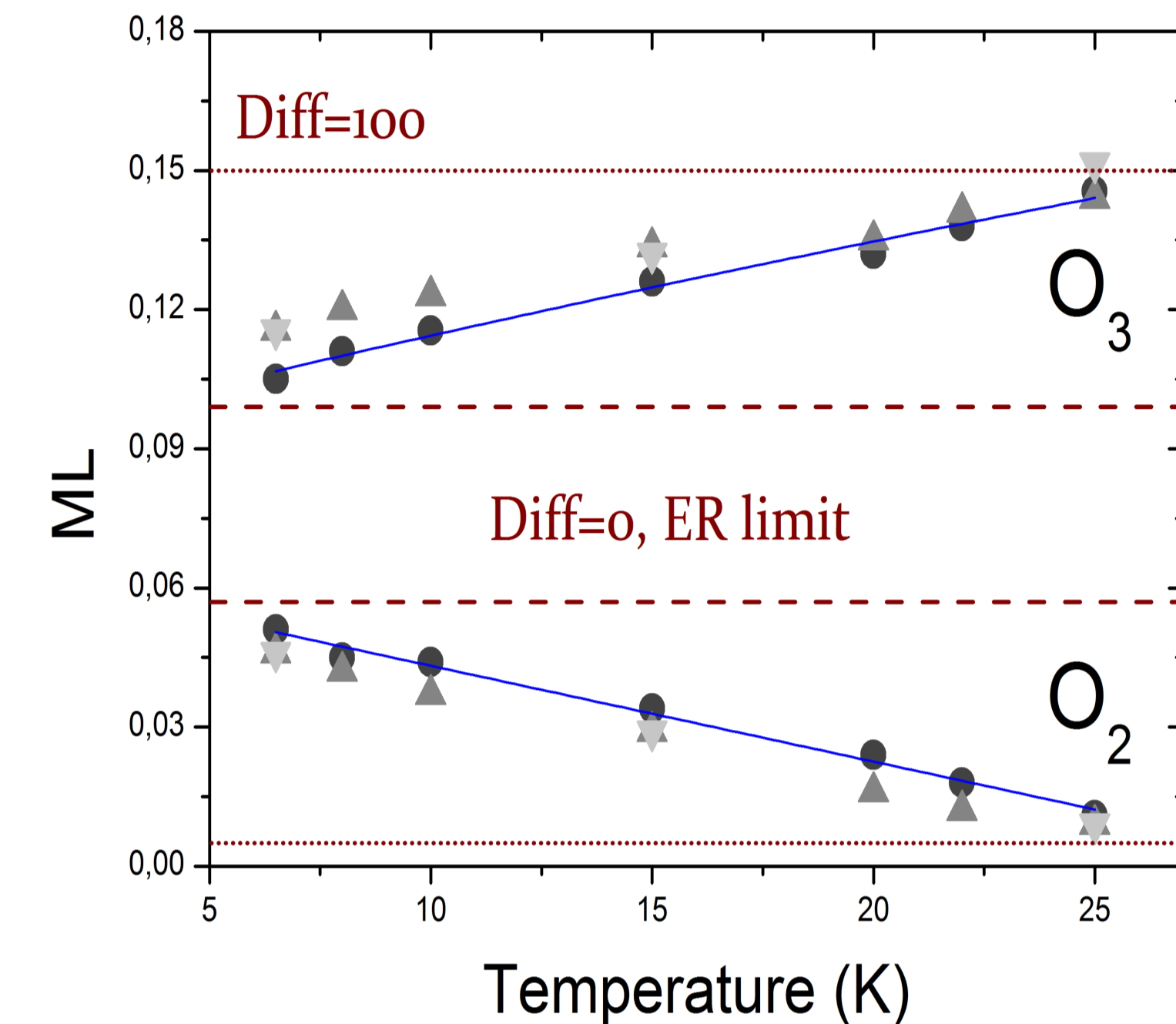
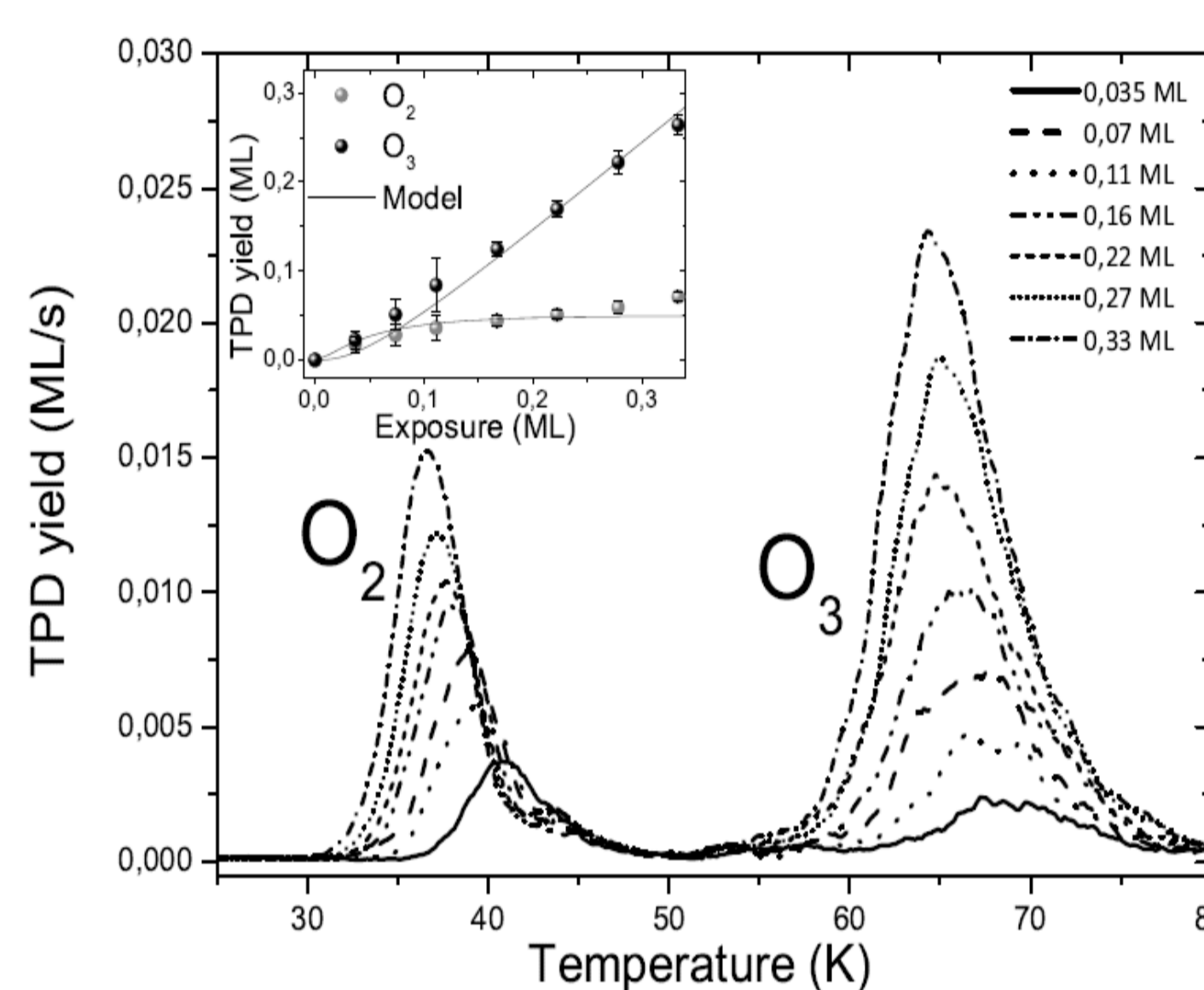
Reflection-Absorption Infrared Spectroscopy of ozone



The O₃ infrared signature does not vary during the TPD, except during desorption. This finding confirms that the reactions occur at 6.3K and do not need any thermal activation.



The desorption peaks of O₂ as the surface is heated up (typical set of thermally programmed experiments, TPD). The O₂ desorption occurs between 35K and 50K, and the ozone desorption is observed between 55K and 75K (directly, or via the O₂⁺ fragments). O desorption is never observed. The circles of the inset represent the area under the curves as a function of exposure doses.



O₂ and O₃ production for a fixed dose (0.15 ML, μ=71%) for various substrate temperatures during the deposition, and for the 3 substrates. The O₃/O₂ ratio increases with the temperature of the substrate, and depends on the substrate itself. For all the experiments, the total number of O atoms measured after a TPD is equal to the number of atoms sent, but partitioned differently between O₂ and O₃. The O₂/O₃ balance is due to the diffusion of atoms.

We have modeled our experiments adapting a classical set of differential equations.

Eley-Rideal

$$\frac{dO}{dt} = 2\mu\phi(1-2O-O_2) - (1-\mu)\phi O$$

$$\frac{dO_2}{dt} = (1-\mu)\phi(1-O) - 2\mu O_2 + 2\mu\phi O$$

$$\frac{dO_3}{dt} = (1-\mu)\phi O + 2\mu\phi O_2$$

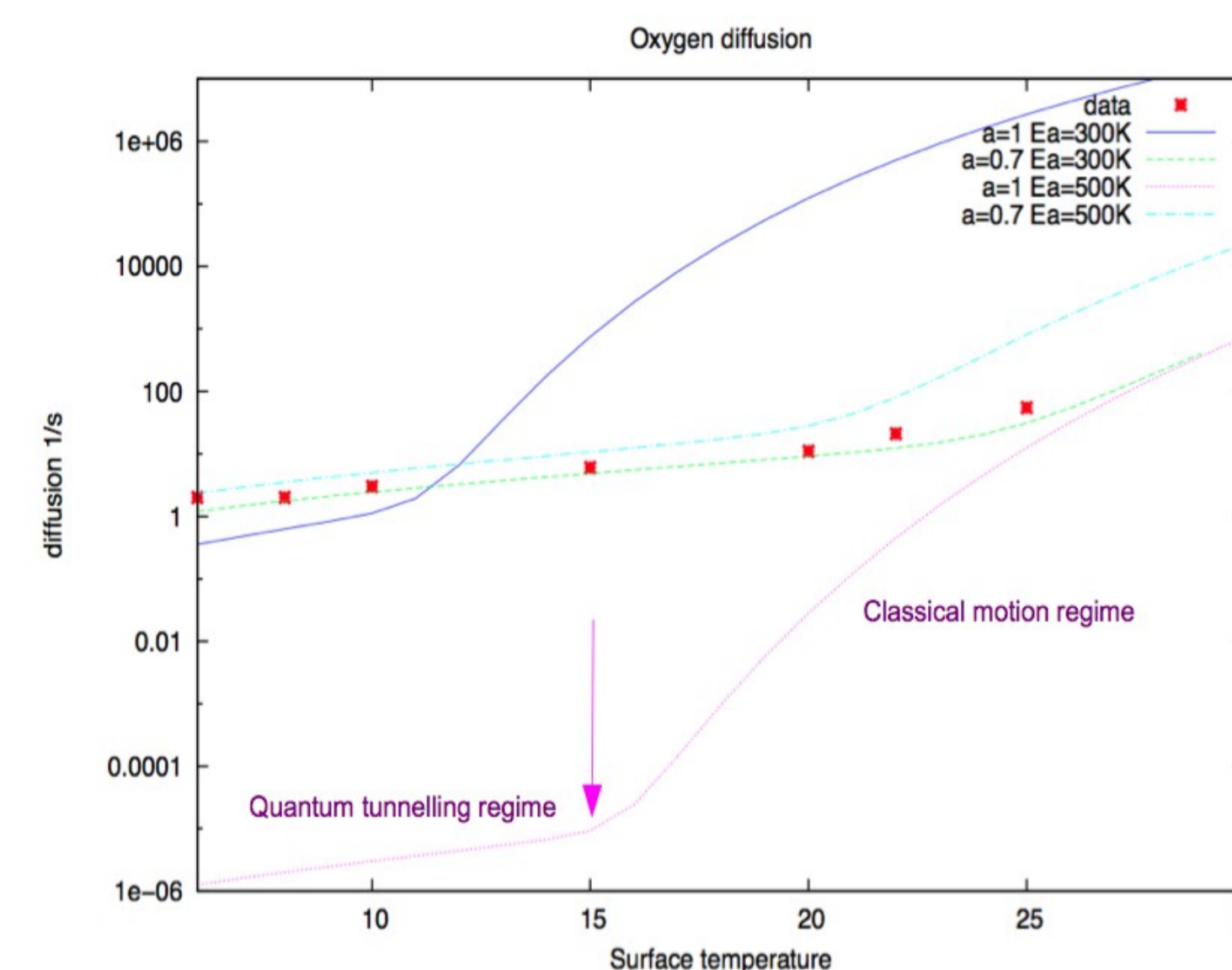
Langmuir-Hinshelwood

$$\frac{dO}{dt} = kOO_2$$

$$\frac{dO_2}{dt} = 2kOO - kOO_2$$

$$\frac{dO_3}{dt} = -4kOO - kOO_2$$

We assume a diffusion-limited reactivity, including the ER mechanism (same efficiency), and possible TPD adjustments due to thermally-induced diffusion. There is only one free physical parameter to adjust, *k*, which represents diffusion. We can reproduce all our data sets, and are able to propose a diffusion law for O as a function of the temperature. The diffusion raises with T, but slowly. The high temperature points (T > 20 K) are overestimated, because at these temperatures O₂ can diffuse as well.



The diffusion can be simulated as in [4]. It includes two components, quantum-tunneling that dominates at low temperatures, and thermal diffusion predominant at higher temperatures.

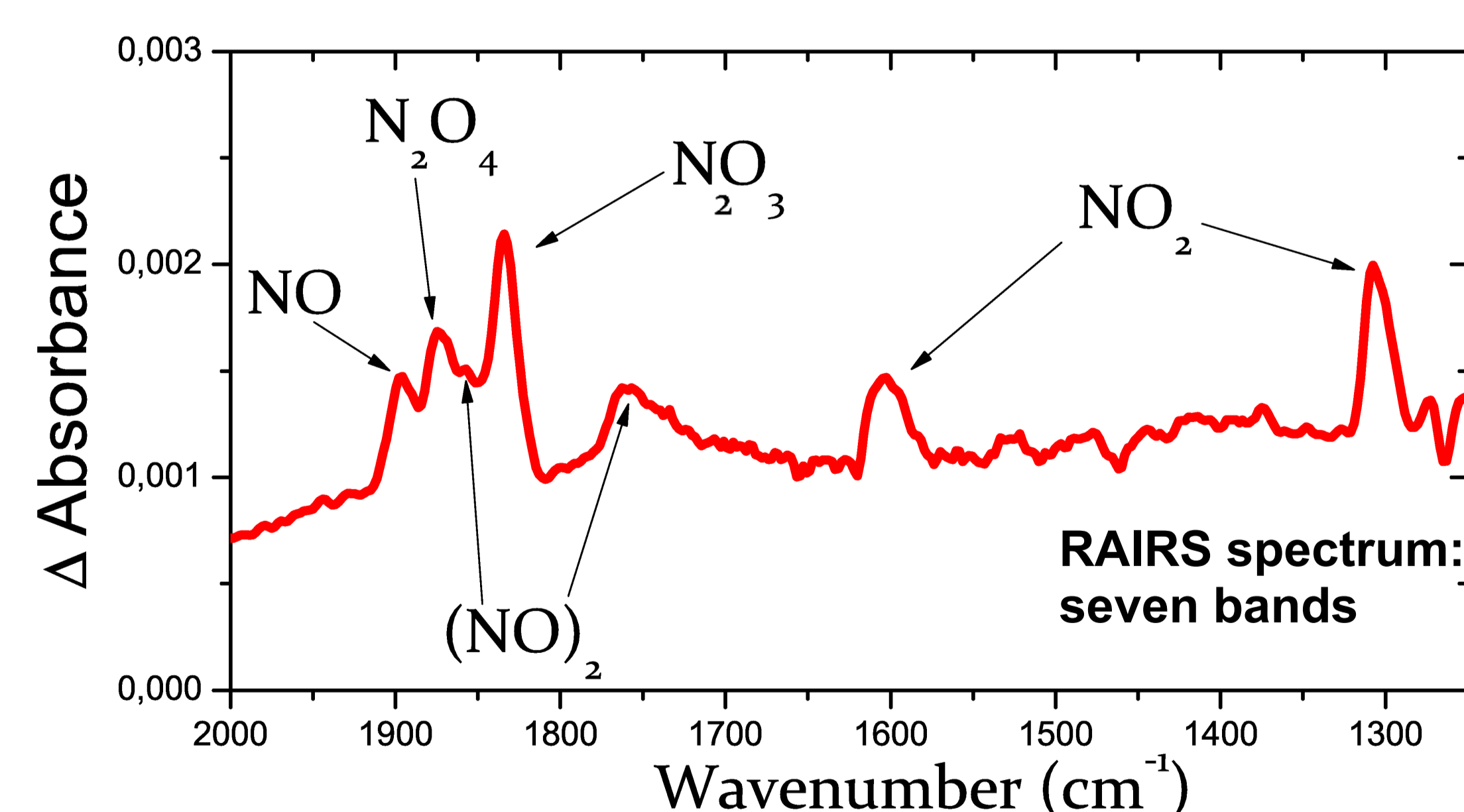
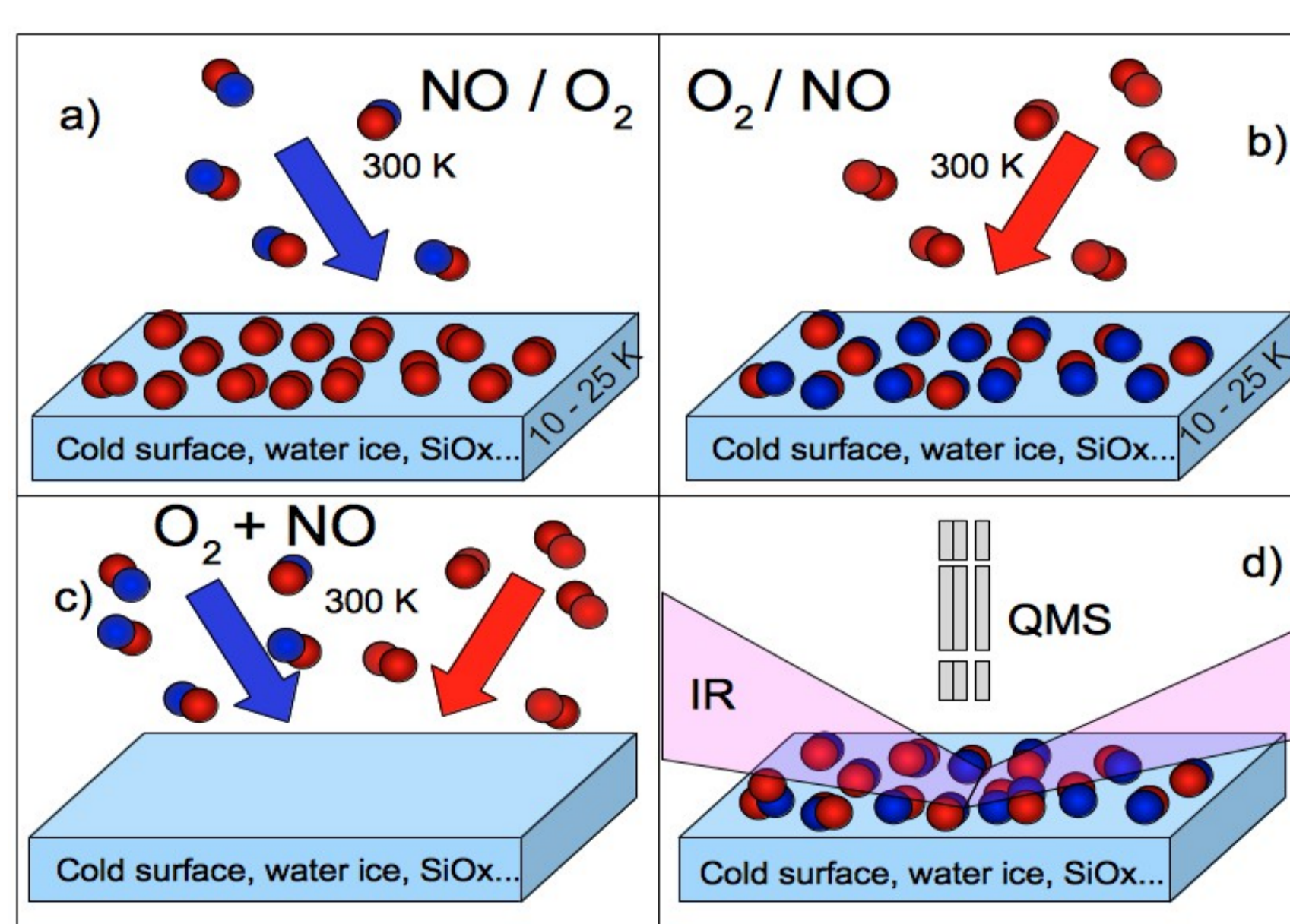
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O₂ reactivity

We focus on the oxidation of NO molecules through O₂ molecules.

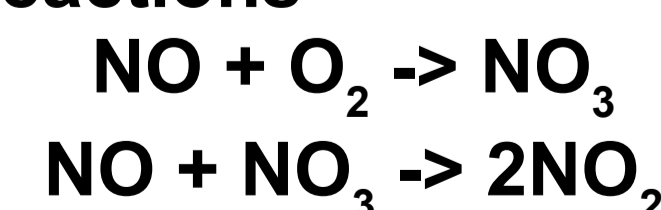
All the experiments suggest formation of NO₃ and NO₂. It is formed with no dependence on the surface morphology and composition. The amount of NO₂ formed, however, is dependent on the order of deposition. Of NO and O₂ on the surface. In addition, experimental data are modelled using a set of rate equations. The model suggests that the NO+O₂ reaction occurs mainly through the Eley Rideal mechanism (independently of the coverage), and that the intermediate species NO₃ reacts with NO molecules to yield nitrogen dioxide.



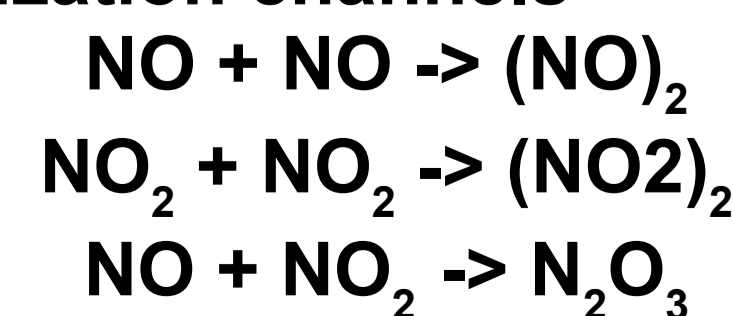
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Red cross in β and curves in γ are obtained by using a rate equations model, considering these reactions



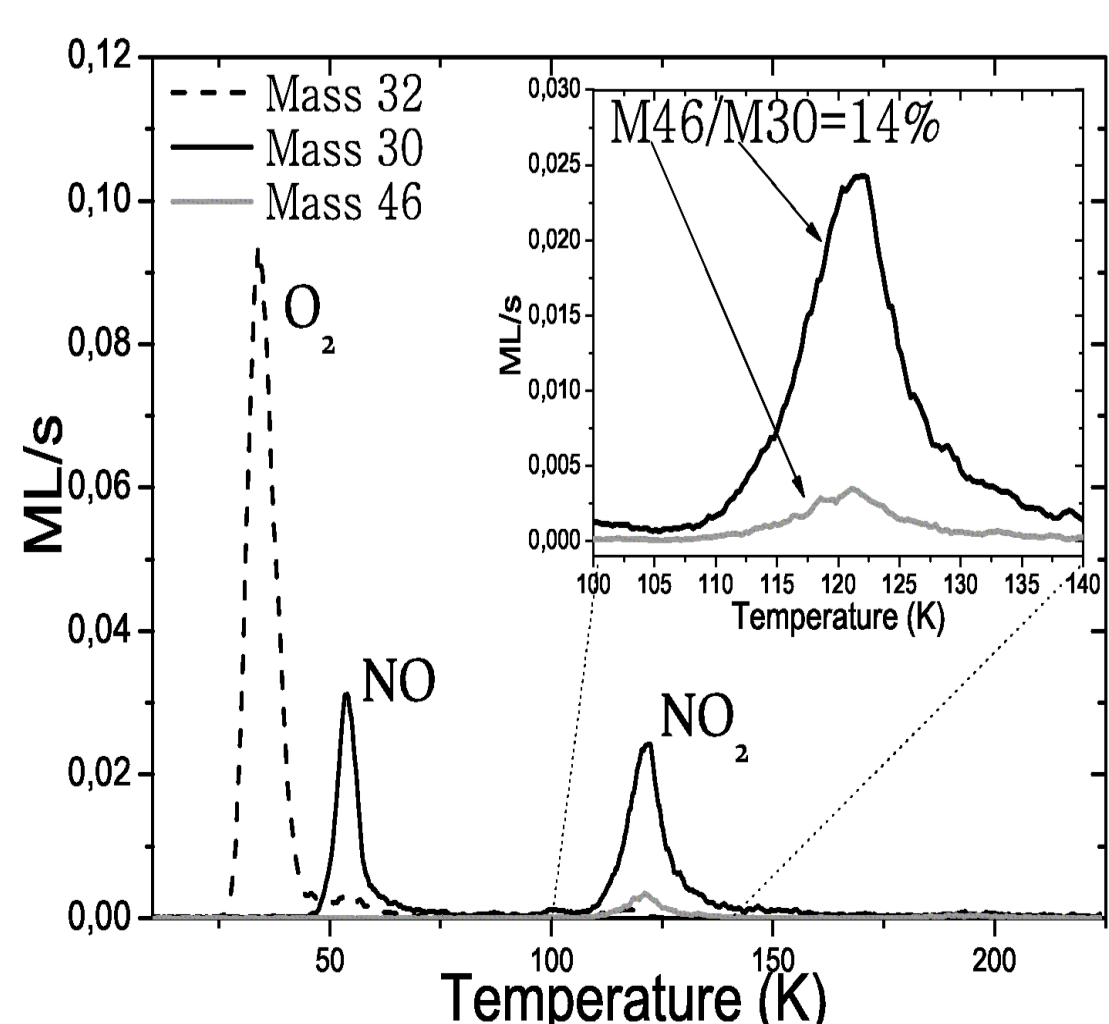
And the subsequent dimerization channels



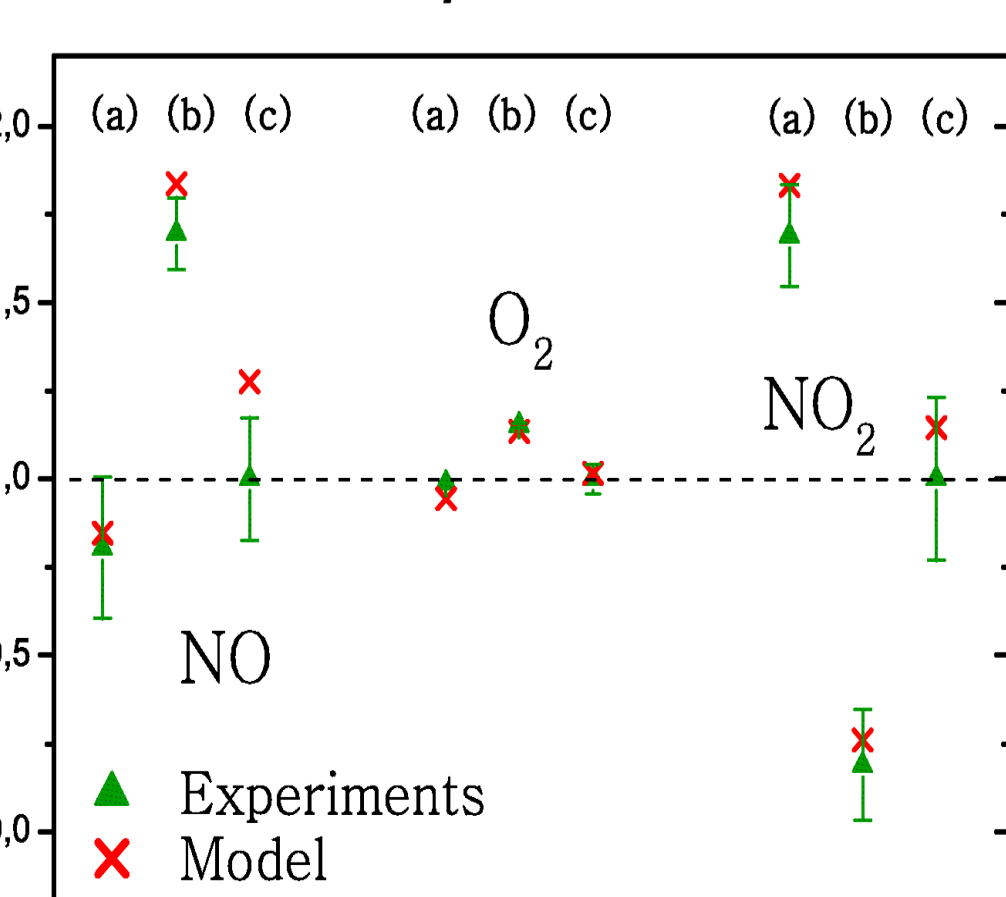
(α)

(β)

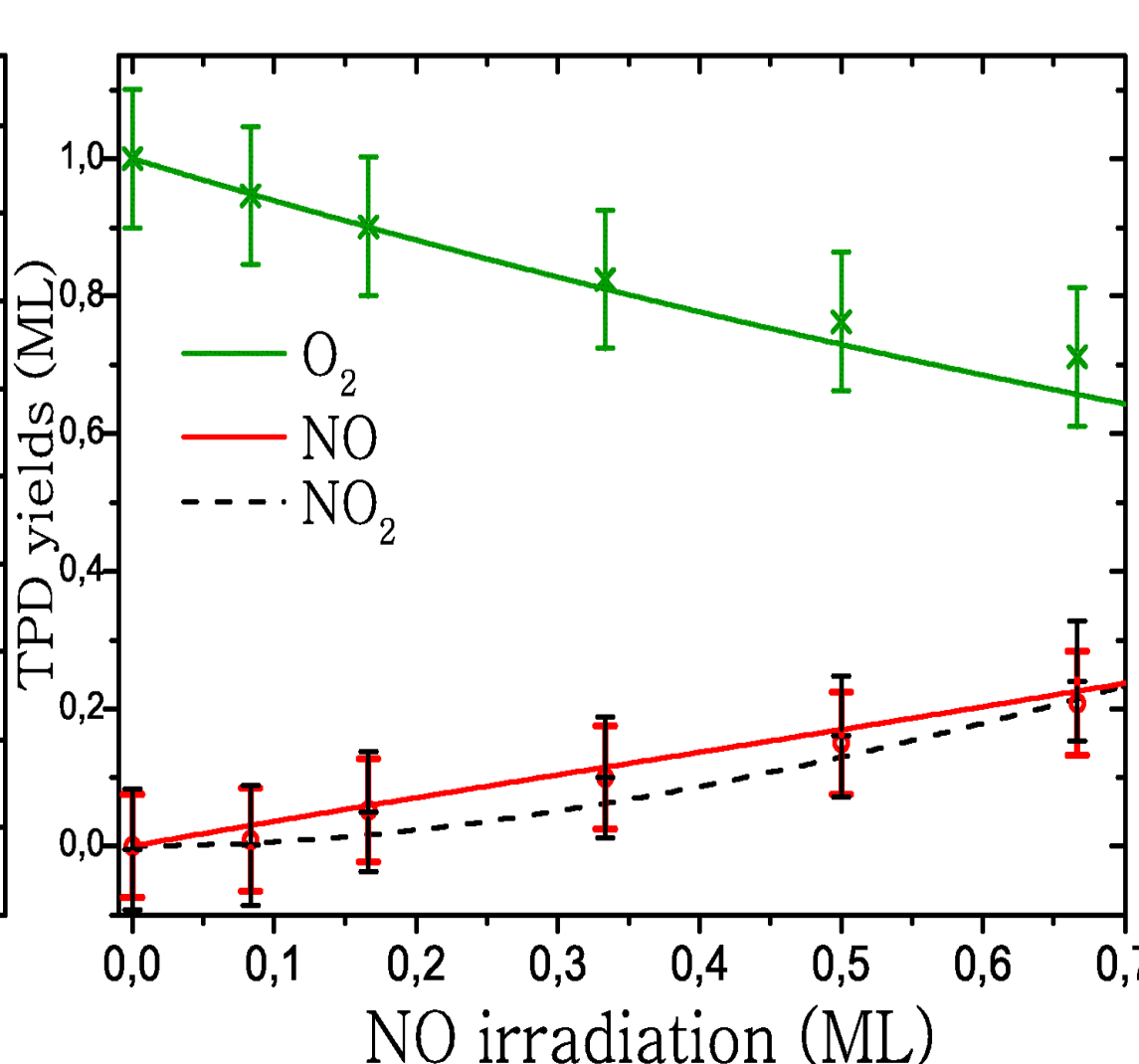
(γ)



TPD curves of masses 30, 32 and 46 u.m.a.



Quantitative amounts (green triangles) obtained for co-deposition (c method) or for the two sequential depositions (a and b methods).



Co-deposition experiments varying NO doses

